EAST Search History

EAST Search History (Prior Art)

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3	photoresist with (pigment or dye) near3 absorb\$3 near3 (UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:04
L2	3	photoresist with (pigment or dye) near3 absorb\$3 near3 (UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:05
L3	2	10/580953	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:06
L4	4	(photoresist or photo near resist\$4 or photo near sensitive) with(pigment or dye or colorant)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:07
L5	3	(photoresist or photo near resist\$4 or photo near sensitive) with(pigment or dye or colorant)near3 absorb\$3 near3(ir or infra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:08
L6	26	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same(pigment or dye or colorant)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:10

L7	41	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same(pigment or dye or colorant)near3 absorb\$3 near3(UV or ultra or ir or infra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:26
L8	41	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same(pigment or dye or colorant)near3 absorb\$3 near3(UV or ultra or ir or infra) and (novola\$2)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:24
L9	25	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same(pigment or dye or colorant)near3 absorb\$3 near3(UV or ultra or ir or infra) and sulphone and ether and aryl	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:25
L10	2	10/140761	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:27
L11	2	10/378553	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:28
L12	408	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32

L13	189	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32
L14	0	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patten\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32
L15	12	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patter\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27
L16	12	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4) with (pigment or dye or colorant) near3 absorb \$3 near3(UV or ultra or ir or infra) and metal near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:33
L17	13	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4) with (pigment or dye or colorant) near3 absorb \$3 near3(UV or ultra or ir or infra) and (conductor or metal) near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:33

L18	114	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and (conductor or metal) near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:35
L19	22	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and plating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27
S1	1	2002/0187267	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/07/26 14:20
S2	1	2002/0187267	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	WON	2011/07/26 14:20
S3	2	10/580953	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:21
S4	0	(photosens\$4 or photoresist\$4)with novolak with patic\$4 with carbon	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	MON	2011/07/26 15:25
S5	0	(photosens\$4 or photoresist\$4)with novolak with patic\$4 with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	MON	2011/07/26 15:25

S6	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	MON Manual Manual Manual Manual Manual Manual Manual Manual Manua	2011/07/26 15:25
S 7	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with convert\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S 8	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with conver\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S 9	3060	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S10	1319	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:27
S11	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with ultra with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:27
S12	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with visible with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28
S13	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28

S14	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28
S15	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S16	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra with novolak	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S17	1	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S18	45	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S19	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with wave	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S20	20	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S21	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and electroless	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30

S22	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and plating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
\$23	20	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S24	129	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:35
\$25	1	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal)with (powder or particulate) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:35
\$26	213	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:36
S27	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate) with absop\$4 and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:36

\$28	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate))and ((carbon or metal) near(powder or particle or particulate) with absop\$4 and pattern \$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	NO.	2011/07/26 15:37
\$29	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:38
S3 0	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate)) and ((iron or metal or pigment or dye) near (powder or particulate) with absop\$4 with (ultra or UV) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR		2011/07/26 15:40
S31	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particulate)) and ((iron or metal or pigment or dye or carbon) near(powder or particulate) with absop\$4 with (ultra or UV) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	N N N N N N N N N N N N N N N N N N N	2011/07/26 15:40

S 32	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near(powder or particle or particulate) with absop\$4 with (ultra or UV)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	N	15:40
S 33	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with(carbon or metal) near(powder or particle or particulate)) and ((iron or metal or pigment or dye or carbon)near(powder or particulate) with absop\$4 with (infra or ir)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26
S 34	0	(photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	nON	2011/07/26

S35	0	photoresist\$4 or photo near resist\$4 or novolak) with (carbon or metal)near	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41
S36	O	photo near resist\$4 or novolak) with	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41